## SARDAR PATEL UNIVERSITY

M.Sc. (Physics)(IIIrd Semester) Examination

Date:22/03/2019, Day: Friday, Time:10:00a.m. to 1:00 p.m.

Subject: Nanoscience and Thin film Physics, Paper No. PS03CPHY02

CBCS(choice based credit system)

Important Note: O.1: Multiple choice questions (MCO) carries one mark each.

70

աւթ	0.2:	Short questions carrie Q.6 : Long questions	s two marks each (attemp	t any seven out of nine)		
	Q.3 to	Q.6: Long questions	carries 12 marks.	Total Marks:		
Q.1	Choose the app	opriate options from	the following in Q.1	(8)		
1	For targeted drug do (a) tungsten nanowi		wing nanoparticles are protubes (c) insulating	eferred (d) magnetic		
2	Three electron energy states are involved to produce the signature of element under observation in which method					
	(a)RBS	(b) AES	(c) XPS	(d) SEM		
3	Which of the follow (a) flash evaporatio		tion technique utilizes RI (c) PECVD	energy ? (d) LECVD		
4	Lithography using (a) photons	do not requ (b) lasers	nire mask to generate patt (c) electron	ern ? (d) X-rays		
5	In coalescence phe following term dec	ich of the				
	(a) area	(b) mass	(c) length	(d) breadth		
6	AFM tips and canti (a) SiN	lever assembly are m (b) GaAs	ade from which material (c) InSb	(d) Ge		
7	For characterizing thin films by X-ray diffraction, how the film should appear to the beam?					
	(a) thin	(b) thicker	(c) ultrathin	(d) None of these		
8	In QCTM techniqu (a)velocity	e which parameter is (b) frequency	used to determine the thi (c)stress	ckness of the film? (d) force		
		Page no. 1		(P.T.O.)		



Q.2	Alight and out of an area area.	(14)		
1	What is the basic principle on which AFM works and which type of tip is used in AFM?			
2	State and write the expression used for particle size determination in particle			
	size analyzer.			
3	Which two conditions must be satisfied to get single electron tunneling?			
4	Define the terms adsorption, desorption and thermal accommodation.			
5	Why molecular beam epitaxy is preferred over liquid phase epitaxy?			
6	Explain how bond energy for the small cluster model is evaluated by Lewis for one, two, three and four atom cluster.			
7	Justify the use of RF sputtering for deposition of thin films of insulating material.			
8	What information does XPS technique gives about the sample?			
9	What are NEMS and MEMS?			
Q.3(a)	Explain principle, working and construction of transmission electron microscope.	(6)		
Q.3(b)	Describe how one can synthesize oxide nanoparticles at laboratory scale.  OR	(6)		
Q.3(b)	By drawing the lay out diagram describe construction and working of Scanning near field optical microscope(SNOM).	(6)		
Q.4(a)	Discuss four different stages of film growth with suitable diagram.	(6) (6)		
Q.4(b)				
Q.4(b)	What is lithography? Explain why X-ray and electron beam lithography are better then photolithography.	(6)		
Q.5(a)	Explain in detail PECVD and LECVD techniques for depositing thin films?	(6)		
Q.5(b)	Discuss in detail MBE method used for depositing monolayer films.	(6)		
- , ,	OR			
Q.5(b)	Explain with suitable diagram magnetron sputtering used for depositing thin films.	(6)		
Q.6(a)	Describe in detail XRD technique used for studying structure of the sample.	(6)		
Q.6(b)	How RHEED differs from LEED? Explain LEED with proper diagrams.	(6)		
	OR	(6)		
Q.6(b)	Explain in detail how SIMS is helpful in studying thin films? Differentiate between static and dynamic SIMS.	(6)		
	Page no. 2			

•

